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	Application No.	Applicant(s)	
Nation of Allowahility	10/620,858	GHOZEIL ET AL.	
Notice of Allowability	Examiner	Art Unit	
	DiLinh Nguyen	2814	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED i i) or other appropriate comm RIGHTS. This application is	n this application. If not included unication will be mailed in due course. THIS	
1. This communication is responsive to 12/21/04.			
2. 🔀 The allowed claim(s) is/are <u>1-17,20 and 25-28</u> .			
3. The drawings filed on 15 July 2003 are accepted by the E	ixaminer.		
 4. Acknowledgment is made of a claim for foreign priority to a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	re been received. re been received in Applicati	on No	
Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		e a reply complying with the requirements	
5. A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EX ves reason(s) why the oath o	AMINER'S AMENDMENT or NOTICE OF or declaration is deficient.	
6. CORRECTED DRAWINGS (as "replacement sheets") mu	ust be submitted.		
(a) I including changes required by the Notice of Draftsper	rson's Patent Drawing Revie	w (PTO-948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examined Paper No./Mail Date	r's Amendment / Comment o	r in the Office action of	
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in			
7. DEPOSIT OF and/or INFORMATION about the dep attached Examiner's comment regarding REQUIREMENT			
: •			
Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB. Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview S Paper No /08), 7. ⊠ Examiner's	Informal Patent Application (PTO-152) Summary (PTO-413), /Mail Date S Amendment/Comment S Statement of Reasons for Allowance	
		HOAI PHAM PRIMARY EXAMINER	

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04)

Application/Control Number: 10/620,858

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DETAILED ACTION

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Matthew Wade on 2/3/05.

Cancel claims 18-19.

REASONS FOR ALLOWANCE

Claims 1-17, 20 and 25-28 are allowed.

The following is an examiner's statement of reasons for allowance:

The prior art of record fail to disclose the combination of all the limitations recited, including the applying a second layer of resist and patterning the second layer of resist using imprint lithography to form a second pattern aligned along a second direction; applying a second ion-masking material over the second pattern, and selectively lifting off the second ion-masking material to leave a second ion mask defined by the second pattern (claim 1) and imprinting a second pattern on the second layer of resist to expose second areas of the first oxide layer aligned along a second direction different form the first direction; covering the patterned second layer of resist and the exposed second areas of the first oxide layer with a gate electrode material; and selectively removing

gate electrode material to leave a gate electrode defined by the second pattern on the first oxide layer (claim 25).

Therefore, the method for fabricating a nanoscopic transistor is neither aniticipated nor rendered obvious over the prior art of record.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to DiLinh Nguyen whose telephone number is (571) 272-1712. The examiner can normally be reached on 8:00AM - 6:00PM (M-F).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (571) 272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

DLN

HOAI PHAM PRIMARY EXAMINER